Diffraction contrast imaging

Lecture 13

Weak beam dark field imaging Simulation of diffraction contrast

- Goal: 'high resolution' diffraction contrast image of defects
- Method: establish a kinematical condition (large s)
- This gives a small ξ_{eff}
- Result is a narrow dislocation image (since this is proportional to ξ_{eff})



Why high-resolution images?

Often want to look at:

- Jogs & kinks
- Separation between partial dislocations
- Interaction between dislocations
- Interaction with other defects & precipitates

Again, these images can help correlate specifics of dislocation motion with overall plastic deformation response



- By setting s 'large' most of the sample is <u>not</u> oriented in a strong Bragg condition
- However, defect locally bends planes back to Bragg angle
- The region over which this occurs is very small, as the strain needed must be large
- Thus the defect image is quite narrow
- The image 'peak' is thus close to the dislocation core
 - Will switch with sign of g



Steps:

- 1. Establish two beam condition with s slightly greater than zero
- 2. Tilt the strong g to the optic axis using dark field tilts
 - You will note that it becomes quite dim
 - You will also see 3g become strong
 - This is purely a geometric effect
- 3. Insert objective aperture & check centering
- 4. Now both BF & WBDF are well established





Nothing 'magical' about the g-3g condition

- It's just one that 'often' works

Any two-beam condition where corresponding DF has s >> 0 will work, and some may work better

For calculation purposes, may need to know s precisely

Measurement method described in W&C text

Resulting WBDF image will have 'weak' intensity

- May require very long exposures
- Resolution limit may be stage drift

A bit of theory

$$I_{g} = \left|\phi_{g}\right|^{2} = \left(\frac{\pi t}{\xi_{g}}\right)^{2} \frac{\sin^{2}\left(\pi s_{eff}^{}t\right)}{\left(\pi s_{eff}^{}\right)^{2}} \qquad s_{eff}^{} = \sqrt{s^{2} + \frac{1}{\xi_{g}^{2}}}$$

If s \gg 0, then s_{eff} \approx s

Resulting image largely insensitive to ξ_{eff} Image is 'kinematical'

$$I \propto \frac{\sin^2\left(\pi s_z t\right)}{\left(\pi s_z\right)^2}$$

So - in most of the image we have kinematical contrast

- $\vec{0}$ and \vec{g} are not strongly coupled

However - local to the defect - the two beams <u>are</u> strongly coupled

- The defect is the connecting link
- Strong dynamical contrast only local to the defect

Bloch wave explanation:

 Defect causes local change in scattering from Bloch Wave #1 to Bloch Wave #2





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Can more readily see dissociation & interaction effects







Inside-outside contrast also sensitive to small changes in s during WBDF imaging



Many more fringes seen in SF images

Spacing very sensitive to s





Strong effect on thickness fringe spacing as well

Large s reduces effective extinction distance ξ_{eff}



slope \downarrow , fringe separation \uparrow , fringe width \uparrow



Simulation of diffraction contrast

Use:

or:

$$\begin{aligned} \frac{d\phi_{g}}{dz} &= \frac{\pi i}{\xi_{g}} \phi_{o} \exp\left[-2\pi i\left(sz + \overset{r}{g} \cdot \overset{r}{R}\right)\right] + \frac{\pi i}{\xi_{o}} \phi_{g} \\ and \\ \frac{d\phi_{o}}{dz} &= \frac{\pi i}{\xi_{g}} \phi_{o} + \frac{\pi i}{\xi_{o}} \phi_{g} \exp\left[2\pi i\left(sz + \overset{r}{g} \cdot \overset{r}{R}\right)\right] \\ \frac{d\phi_{o}}{dz} &= \frac{\pi i}{\xi_{o}} \phi_{g} \\ and \\ \frac{d\phi_{g}}{dz} &= \frac{\pi i}{\xi_{o}} \phi_{o} + \left[2\pi i\left(sz + \overset{r}{g} \cdot \frac{d\overset{r}{R}}{dz}\right)\right] \phi_{g} \end{aligned}$$



Figure 8.4. Theoretical profiles of thickness fringes. (a) No absorption. (b) $\xi_g/\xi_g' = 0.05$. (c) $\xi_g/\xi_g' = 0.10$. Note the reduced visibility of the fringes in the thick regions of (c). Continuous and broken lines refer to bright-field and dark-field images respectively (From Hashimoto, Howie and Whelan, 1962, by courtesy of The Royal Society)

Thickness fringes



Figure 8.5. 'Rocking Curves' computed on the two-beam theory for a crystal of thickness $t=4\xi_g$. Full curves are bright-field images; broken curves are dark-field images. The dark-field images are symmetrical about $w=s\xi_g=0$. (a) No absorption, $\xi_g/\xi_g'=0$. (b) $\xi_g/\xi_g'=0.05$. (c) $\xi_g/\xi_g'=0.10$. The curves in (a) are complementary. Note the asymmetry of the bright-field images in (b) and (c) (corresponding to either edge of the dark band at D in Figure 8.3), and the reduced amplitude of the which items in (c). In (b) and (c) $\xi_g' = \xi_g'$

subsidiary oscillations in (c). In (b) and (c) $\xi_0' = \xi_g'$ (From Hashimoto, Howie and Whelan, 1962, by courtesy of The Royal Society)

Obviously, can produce simulated images by calculating ϕ_o and ϕ_g along each column





Figure 10.9. Computed stacking fault image profile for $\alpha = -2\pi/3$ with anomalous absorption effects included, $t|\xi_{g}=5, \xi_{0}'=\xi_{g}',$ $\xi_{g}|\xi_{g}'=0.07, w=0$. Bright- and darkfield images are shown as continuous and broken lines respectively (From Hashimoto, Howie and Whelan, 1960, by courtesy of The Philosophical Magazine)



Figure 10.8. Computed stacking fault image profile for $\alpha = +2\pi/3$ with anomalous absorption effects included, $t/\xi_g = 7.25$, $\xi_o' = \xi_g'$, $\xi_g/\xi_g' = 0.075$, w = -0.2. Bright- and dark-field images are shown as continuous and broken lines respectively (From Hashimoto, Howie and Whelan, 1962,

by courtesy of The Royal Society)

Dislocations show relatively sharp fall-offs in contrast

Due to the nature of $\frac{dR}{dz}$



Figure 11.11. Computed bright-field images of mixed dislocations. The image width depends on the value of the parameter p shown for each curve. See text for discussion (From Howie and Whelan, 1962, by courtesy of The Royal Society)





Figure 11.4. Computed bright-field (continuous line) and dark-field (broken line) images for a screw dislocation in the middle of a thick foil with $t = 8\xi_g$, $\mathbf{g} \cdot \mathbf{b} = 1, \ \xi_g / \xi_g' = 0.1$. In (a) w = 0; in (b) w = 0.3(From Howie and Whelan, 1962, by courtesy of The Royal Society)



Figure 11.5. Computed bright- and dark-field images for an edge dislocation in the middle of a thick foil with $t=8\xi_{a}$, $\mathbf{g} \cdot \mathbf{b}=1, \xi_{a}/\xi_{a}'=0\cdot1, w=0$. Compare with Figure 11.4a

Edge

"A method for simulating electron microscope dislocation images," *Schublin R., Stadalmann P.,* Materials Science and Engineering, A 164 (1993) 378-378

<u>Computed Electron Micrographs and Defect</u> <u>Identification</u>, *Head A.K., Humble P., Clarebrough L.M., Morton A.J.* and *Forwood C.T.,* North-Holland Publishing Company, Amsterdam, 1973

CUFOUR:

-http://cecm.insa-lyon.fr/CIOL/cufour.html

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"SIMCON" -

A program that allows one to use the output form FEM modeling to generate simulated diffraction contrast

K. Janssens, Ultramicroscopy, 45, 323, 1992.

J. Demarest, et al., Appl. Phys. Lett., 77, 412, 2000.

Li, et al., Appl. Phys. Lett. 87, 222111, 2005.







FIG. 3. (Color) ANSYS stress plot of *y*-axis stresses (vertical in the plane of the page) surrounding the shallow isolation trench structure. Note: entire FE model not shown.